

## **IN THE CLAIMS:**

### **Amendments to the Claims**

Please amend claims 8 and 9 as shown below.

### **Listing of Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 1-7 (canceled)

8. (currently amended) An apparatus for plasma processing of a nonvolatile material which has a vacuum vessel forming a plasma producing part, a gas supplying means for supplying a gas to the vacuum vessel, an antenna generating an electric field in the plasma producing part, a Faraday shield provided at an outer periphery of the vacuum vessel, a high-frequency electric source supplying a high-frequency electric power to the antenna and the Faraday shield, and an end point determination and detection means, said end point determination and detection means detecting the end point of cleaning of the inner wall of the vacuum vessel by detecting emission wavelength of reaction products generated when the cleaning of the vacuum vessel is effected utilizing a gas containing at least boron trichloride and chlorine supplied to the vacuum vessel and a voltage of at least 500 V supplied to the Faraday shield.

9. (currently amended) An apparatus for plasma processing of a nonvolatile material which has a vacuum vessel forming a plasma producing part, a gas supplying means for supplying a gas to the vacuum vessel, an antenna generating an electric field in the plasma producing part, a Faraday shield provided at an outer periphery of the vacuum vessel, a high-frequency electric source supplying a high-frequency electric power to the antenna and the Faraday shield,

and an end point determination and detection means, said end point determination and detection means detecting the end point of cleaning of the inner wall of the vacuum vessel by detecting emission wavelength of a material of products formed from the vacuum vessel generated when the cleaning of the vacuum vessel is effected utilizing a gas containing at least boron trichloride and chlorine supplied to the vacuum vessel and a voltage of at least 500 V supplied to the Faraday shield.